We claim:

1. A stripping composition consisting essentially of

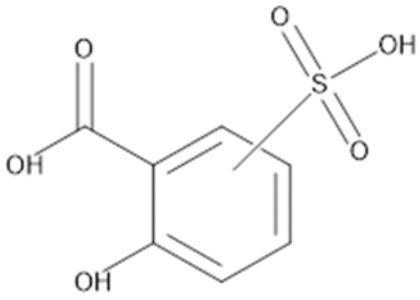
one of at least one sulfosalicylic acids having structure (I), its hydrate, or a mixture of this sulfosalicylic acid and its hydrate;

a primary solvent selected from acetone, and methyl ethyl ketone, or a mixture of these solvents,

a secondary solvent which is a glycolic derivative, or a mixture of at least two glycolic derivatives, wherein said secondary solvent is selected from the group consisting of alkylenediols, oligo(alkyleneoxyalkylene) diols [HO-(alkylene-O-alkylene-O)n-H] (n= 1 to 4), monoalkyl ethers of alkylenediols, monoalkyl ethers of oligo(alkyleneoxyalkylene) diols, dialkyl ethers of alkylenediols, dialkyl ethers of oligo(alkyleneoxyalkylene) diols, alkylenediols in which one of the hydroxy groups is functionalized as an alkylcarboxylate and the other is functionalized as an ether, oligo(alkyleneoxyalkylene) diols in which one of the hydroxy groups is functionalized as an alkylcarboxylate and the other is functionalized as an ether, alkylenediols in which one of the hydroxy groups is functionalized as an alkylcarboxylate, oligo(alkyleneoxyalkylene) diols in which one of the hydroxy groups is functionalized as an alkylcarboxylate, alkylenediols in which both of the hydroxy groups are functionalized as alkylcarboxylates and oligo(alkyleneoxyalkylene) diols in which both of the hydroxy groups is functionalized as alkylcarboxylates;

and an optional surfactant,

wherein these constituents form at least 90 wt% of the composition;

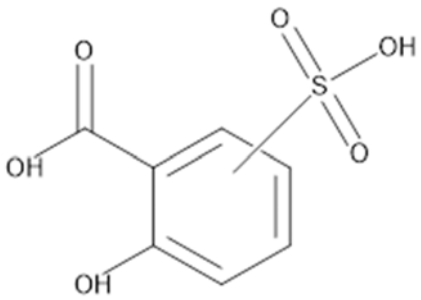


(I).

2. The composition of claim 1 consisting of

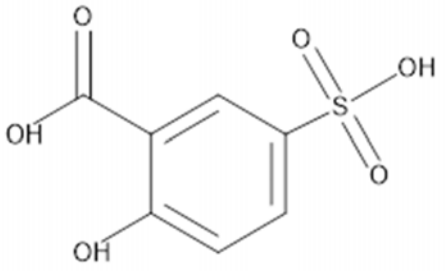
one of at least one sulfosalicylic acids having structure (I), its hydrate, or a mixture of this sulfosalicylic acid and its hydrate;

a primary solvent selected from acetone, and methyl ethyl ketone, or a mixture of these solvents,
a secondary solvent which is a glycolic derivative, or a mixture of at least two glycolic derivatives, and
an optional surfactant;



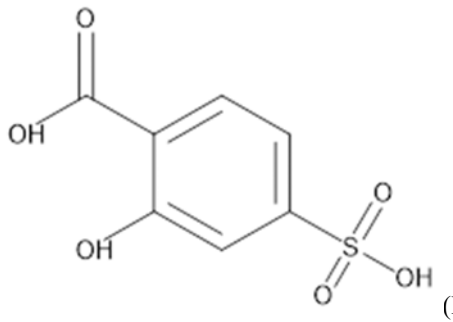
(I).

3. The composition of claim 1 or 2, wherein said sulfosalicylic acid is one having structure (Ia) or its hydrate:



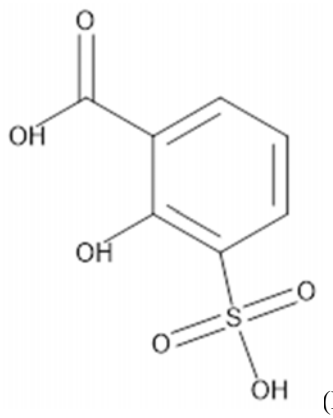
(Ia).

4. The composition of claim 1 or 2, wherein said sulfosalicylic acid is one having structure (Ib) or its hydrate:



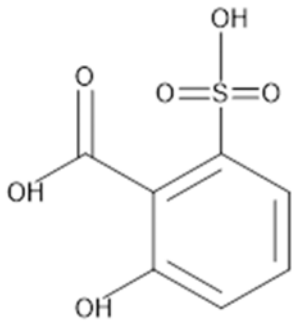
(Ib),

5. The composition of claim 1 or 2, wherein said sulfosalicylic acid is one having structure (Ic) or its hydrate:



(Ic).

6. The composition of claim 1 or 2, wherein said sulfosalicylic acid is one having structure (Id) or its hydrate:



(Id).

7. The composition of any one of claims 1 to 6, wherein said primary solvent is acetone or methyl ethyl ketone.

8. The composition of any one of claims 1 to 6, wherein said primary solvent is a mixture of acetone and methyl ethyl ketone.

9. The composition of any one of claims 1 to 8, wherein said secondary solvent is selected from either a solvent selected from the group consisting of PGME, PGMEA, propylene glycol, dipropylene glycol (IV), dipropylene glycol mono methyl ether (II), dipropylene glycol dimethyl ether (III), or a mixture of at least two of these solvents.

10. The composition of claim 9, wherein said secondary solvent is dipropylene glycol mono methyl ether (II).

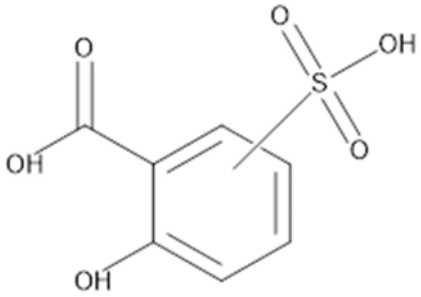
11. A composition consisting essentially of

one of at least one sulfosalicylic acids having structure (I), its hydrate, or a mixture of this sulfosalicylic acid and its hydrate;

a primary solvent selected from acetone, and methyl ethyl ketone, or a mixture of these solvents,

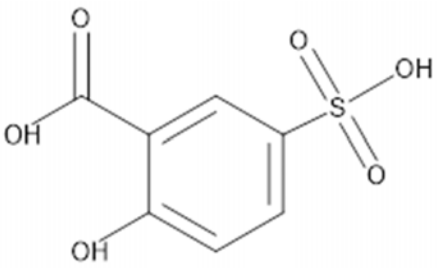
optionally a secondary solvent which is a glycolic derivative, or a mixture of at least two glycolic derivatives, and

optionally a surfactant;

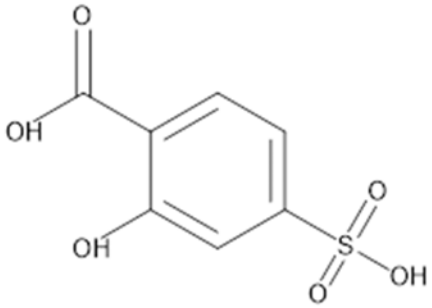


(I),

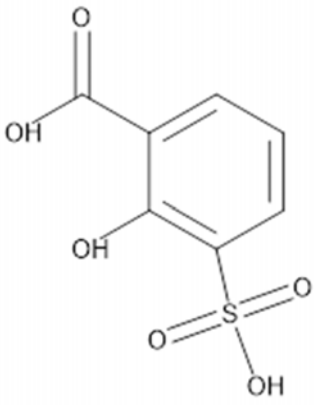
wherein the sulfosalicylic acid of structure (I) or its hydrate is selected from ones having structures (Ib), (Ic), (Id) or its hydrate, mixtures thereof, and mixtures thereof with ones having structure (Ia) or its hydrate



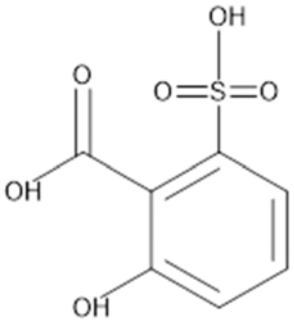
(Ia),



(Ib),



(Ic),



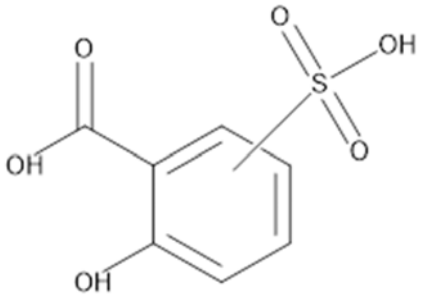
(Id).

12. The composition of claim 11 consisting of

one of at least one sulfosalicylic acids having structure (I), its hydrate, or a mixture of this sulfosalicylic acid and its hydrate;

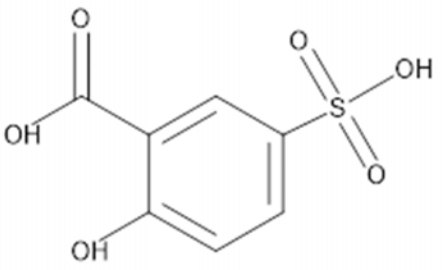
a primary solvent selected from acetone, and methyl ethyl ketone, or a mixture of these solvents,

optionally a secondary solvent which is a glycolic derivative, or a mixture of at least two glycolic derivatives, and optionally a surfactant;

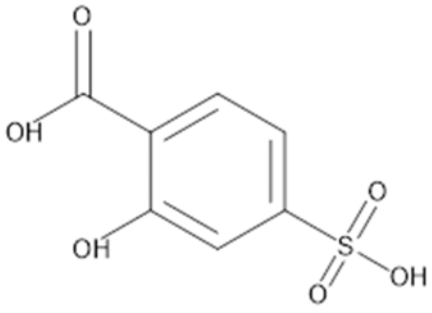


(I),

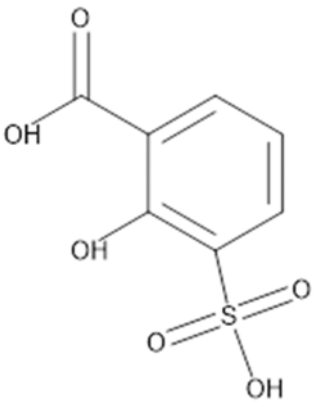
wherein the sulfosalicylic acid of structure (I) or its hydrate is selected from ones having structures (Ib), (Ic), (Id) or its hydrate, mixtures thereof, and mixtures thereof with ones having structure (Ia) or its hydrate



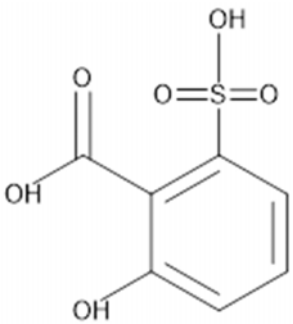
(Ia),



(Ib),



(Ic),



(Id).

13. A process comprising the steps:

i) thermally adjusting a compositionconsisting essentially of

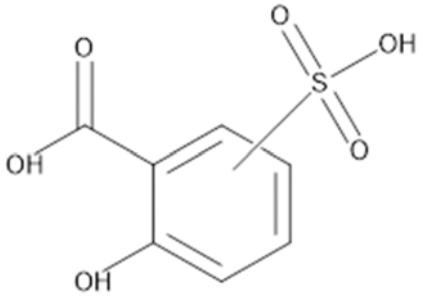
one of at least one sulfosalicylic acids having structure (I), its hydrate, or a mixture of this sulfosalicylic acid and its

hydrate;

a primary solvent selected from acetone, and methyl ethyl ketone, or a mixture of these solvents,

an optional secondary solvent which is a glycolic derivative, or a mixture of at least two glycolic derivatives, and

an optional surfactant;



(I),

to be at a temperature of 15°C to 80°C, resulting in a thermally adjusted composition

ii) treating a substrate coated with a photoresist film with said thermally adjusted composition for a time from 1 minutes to 60 minutes, until a substrate with a removed photoresist film, results,

iii) after step ii), rinsing said substrate with a removed photoresist film with one of isopropyl alcohol, a mixture of isopropyl alcohol and water, or water to remove any residual composition from step ii), producing a clean substrate,

iv) drying said clean substrate.

14. The process of claim 13, wherein the composition is the composition according to any one of claims 1 to 12.

15. The use of the composition of any one of claims 1 to 12 or as defined in claim 13 for removing a photoresist film from a substrate.